

13.5nm, 25.4mm Dia, 5° AOI, EUV Flat Mirror



Extreme Ultraviolet (EUV) Flat Mirrors

Stock #38-759 10 In Stock

-

1

+

€2.750⁰⁰

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General

Flat Mirror

Type:

Physical & Mechanical Properties

25.40 ±0.25

Diameter (mm):

6.35 ±0.508

Thickness (mm):

Back Surface:

Commercial Polish	
90	Clear Aperture (%):
Fine Ground	Edges:
3	Parallelism (arcmin):
<5 RMS	Surface Roughness (□):
Optical Properties	
Metal/Semiconductor	Coating Type:
Mo/Si Multilayer Top Layer: Silicon	Coating:
λ/10 @ 632.8nm	Surface Flatness (P-V):
13.18 - 13.68	Wavelength Range (nm):
13.5	Design Wavelength DWL (nm):
Single Crystal Silicon	Substrate: □
5	Angle of Incidence (°):
R _{abs} >60% @ 13.5nm, 5° (s-pol)	Coating Specification:
10-5	Surface Quality:
>60	Reflection at DWL (%):
0.50	Full Width-Half Max FWHM (nm):
Electrical	
92	Center Energy (eV):
Regulatory Compliance	
View	Certificate of Conformance:

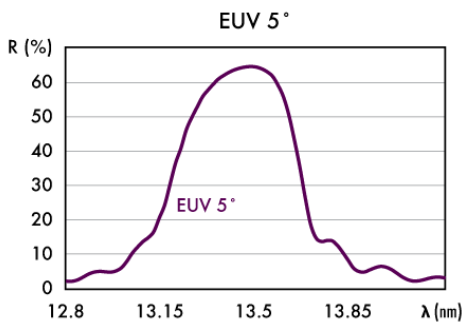
Product Details

- Maximum Achievable Reflection at 13.5nm
- Designed for EUV Beam Steering and Harmonic Separation
- 5° and 45° AOI Versions Available

Extreme Ultraviolet (EUV) Flat Mirrors are multilayer mirrors designed for maximum achievable reflectance at the design wavelength and angle of incidence. These mirrors feature a coating deposited on a super-polished single crystal silicon substrate and surface roughness less than 3□ RMS. The 45° AOI mirrors are useful for steering s-polarized beams, while the 5° AOI mirrors may be used with unpolarized beams. Applications for EUV mirrors include Coherent Diffractive Imaging (CDI) and materials science research. Extreme Ultraviolet (EUV) Flat Mirrors can also serve as harmonic selectors for High Harmonic Generation (HHG) beams.

Note: Test data from each mirror's production run sample included.

Technical Information



Compatible Mounts

